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(54) Title (EN): FLEXIBLE SUBSTRATE OF FLEXIBLE OLED DISPLAY PANEL AND MANUFACTURING METHOD THEREOF

(54) Title (FR): SUBSTRAT SOUPLE DE PANNEAU D'AFFICHAGE OLED SOUPLE ET SON PROCÉDÉ DE FABRICATION

(54) Title (ZH): 柔性OLED显示面板的柔性基底及其制备方法

(57) Abstract:

(EN): Provided is a manufacturing method of a flexible substrate of an OLED display panel, comprising the following steps: S10, providing a first polyimide layer (201); S20, manufacturing a first silicon oxide layer (202) on a surface of the first polyimide layer (201); S30, manufacturing a second silicon oxide layer (203) on a surface of the first silicon oxide layer (202); S40, manufacturing an amorphous silicon layer (204) on a surface of the second silicon oxide layer (203); and S50, manufacturing a second polyimide layer (205) on a surface of the amorphous silicon layer (204).

(FR): La présente invention concerne un procédé de fabrication d'un substrat souple d'un panneau d'affichage OLED, comprenant les étapes suivantes consistant : S10, à fournir une première couche de polyimide (201) ; S20, à fabriquer une première couche d'oxyde de silicium (202) sur une surface de la première couche de polyimide (201) ; S30, à fabriquer une seconde couche d'oxyde de silicium (203) sur une surface de la première couche d'oxyde de silicium (202) ; S40, à fabriquer une couche de silicium amorphe (204) sur une surface de la seconde couche d'oxyde de silicium (203) ; et S50, à fabriquer une seconde couche de polyimide (205) sur une surface de la couche de silicium amorphe (204).

(ZH): 一种OLED显示面板的柔性基底制备方法,方法包括以下步骤:S10,提供第一聚酰亚胺层(201);S20,在第一聚酰亚胺层(201)表面制备第一氧化硅层(202);S30,在第一氧化硅层(202)表面制备第二氧化硅层(203);S40,在第二氧化硅层(203)表面制备非晶硅层(204);S50,在非晶硅层(204)表面制备第二聚酰亚胺层(205)。

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